

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

PATENT APPLICATION

In re Application

SC/Serial No.: SEE SCHEDULE A SEE SCHEDULE A

Filed: Title:

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**CHANGE OF ADDRESS** 

Commissioner for Patents Washington, DC 20231

Sir:

I am the attorney of record for the patents and patent applications listed on Schedule A attached hereto. Please be notified that my address has changed to the following:

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Please send all future correspondence concerning the patent and patent applications listed on Schedule A to the above address.

12-17-02

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## SCHEDULE A

## LIST OF ISSUED PATENTS

| Title   | Filing Date | U.S. Serial No. | Issue Date | Patent No. | Old (BDSM)<br>Attorney<br>Docket No. | New Attorney<br>Docket No. |
|---|-------------|-----------------|------------|------------|--------------------------------------|----------------------------|
| Null Test Fourier Domain Alignment Technique<br>for Phase-Shifting Point Diffraction Interferometer | 1/12/1999   | 09/229,449      | 8/29/2000  | 6,111,646  | 015780-024                           | LBLL-01024US0              |
| Phase-Shifting Point Diffration Interferometer<br>Mask Designs                                      | 10/21/1998  | 09/176,617      | 10/23/2001 | 6,307,635  | 015780-025                           | LBLL-01025US0              |
| Phase-Shifting Point Diffraction Interferometer<br>Grating Designs                                  | 10/21/1998  | 09/176,695      | 2/27/2001  | 6,195,169  | 015780-027                           | LBLL-01027US0              |
| Phas-Shifting Point Diffraction Interferometer<br>Focus-Aid Enhanced Mask                           | 7/26/1999   | 09/361,780      | 11/21/2000 | 6,151,115  | 015780-028                           | LBLL-01028US0              |
| Dual-Domain Point Diffraction Interferometer  | 4/27/1999   | 09/300,539      | 8/8/2000   | 6,100.978  | 015780-030                           | I BI I -010301150          |
| In Situ Alignment System for Phase Shifting Point-diffraction Interferometry                        | 6/2/1999    | 09/324,903      | 9/12/2000  | 6,118,535  | 015780-031                           | LBLL-01031US0              |
| Phase-Shifting Point Diffraction Interferometer<br>Phase Grating Designs                            | 10/14/1999  | 09/419,703      | 7/24/2001  | 6,266,147  | 015780-032                           | LBLL-01032US0              |
| Interferometric At-Wavelength Flare<br>Characterization of EUV Optical System                       | 7/28/2000   | 09/627,533      | 5/15/2001  | 6,233,056  | 015780-033                           | LBLL-01033US0              |
| Method of Fabricating Reflection-Mode EUV-Diffraction Elements                                      | 12/5/2000   | 06/730,970      | 5/21/2002  | 6,392,792  | 015780-039                           | LBLL-01039US0              |
|   |             |                 |            |            |                                      |                            |

SCHEDULE A

## LIST OF PENDING PATENT APPLICATIONS

| Title  | Filing Date | U.S. Serial No. | Old (BDSM) Attorney<br>Docket No. | New (FDML) Attorney<br>Docket No. |
|--|-------------|-----------------|-----------------------------------|-----------------------------------|
| Method and Apparatus for Inspecting Reflection Masks for Defects                 | 11/17/1998  | 09/193,198      | 015780-026                        | LBLL-01026US0                     |
| System for Interferometric Distortion<br>Measuremens That Define an Optical Path | 5/11/2000   | 09/569,168      | 015780-029                        | LBLL-01029US0                     |
| Dual-Domain Lateral Shearing Interferometer                                      | 8/4/2000    | 09/632,631      | 015780-034                        | LBLL-01034US0                     |
| Hybrid Shearing and Phase-Shifting Point Diffraction Interferometer              | 7/17/2000   | 09/617,719      | 015780-035                        | LBLL-01035US0                     |
| Method of Fabricating Reflection-Mode EUV Diffusers                              | 4/30/2001   | 09/846,150      | 015780-040                        | LBLL-01040US0                     |
| Apparatus for Generating Partially Coherent<br>Radiation                         | 8/30/2001   | 09/944,391      | 015780-041                        | LBLL-01041US0                     |
| A Holographic Illuminator for Synchrotron-Based Projection Lithography Systems   | 10/16/2001  | 09/981,500      | 015780-042                        | LBLL-01042US0                     |
| Synchrotron-Based EUV Lithography Illuminator Simulator                          | 6/5/2002    | 10/163,479      | 015780-043                        | LBLL-01043US0                     |
| Diffractive Optical Element for Extreme<br>Ultraviolet Wavefront Control         | 9/17/2001   | 09/956,160      | 015780-044                        | LBLL-01044US0                     |
|  |             |                 |                                   |                                   |